

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1-26 (canceled)

Claim 27 (previously presented): A method for removing a deposited film from a wall inside a chamber, said method comprising:

providing a hot element, said hot element disposed away from said wall and said deposited film, said hot element having at least a surface which is composed of platinum;

heating said hot element to 400° C. or higher without generating a plasma;

supplying said chamber with a cleaning gas containing at least one of a fluorine atom and a chlorine atom, and first contacting said hot element with said gas to thereby activate said gas;

thereafter contacting the deposited film with said activated cleaning gas and converting said deposited film into a gaseous substance; and

removing said gaseous substance from said chamber.

Claim 28 (previously presented): The method according to claim 27, wherein said chamber comprises a CVD apparatus and the method further comprises:

heating the hot element;

supplying a material gas to the chamber;

contacting the material gas with the hot element to cause decomposition and/or activation of the material gas by said hot element; and

forming the deposited film which comprises at least one element from said material gas on a substrate.

Claim 29 (previously presented): The method according to claim 27, wherein at least a part of a surface of an inner structure of said chamber is covered with platinum.

Claim 30 (previously presented): The method according to claim 28, wherein at least a part of the surface of an inner structure of said chamber is covered with platinum.

Claim 31 (previously presented): The method according to claim 27, wherein said cleaning gas is a gas containing at least one of fluorine (F₂), chlorine (Cl₂), nitrogen trifluoride (NF₃), carbon tetrafluoride (CF₄), hexafluoroethane (C₂F₆), octafluoropropane (C₃F₈), carbon tetrachloride (CCl₄), pentafluorochloroethane (C₂ClF₅), trifluorochlorine (ClF₃), trifluorochloromethane (CClF₃), and sulfur hexafluoride (SF₆), and mixtures thereof.

Claim 32 (previously presented): The method according to claim 28, wherein said cleaning gas is a gas containing at least one of fluorine (F₂), chlorine (Cl₂), nitrogen trifluoride (NF₃), carbon tetrafluoride (CF₄), hexafluoroethane (C₂F₆), octafluoropropane (C₃F₈), carbon tetrachloride (CCl₄), pentafluorochloroethane (C₂ClF₅), trifluorochlorine (ClF₃), trifluorochloromethane (CClF₃), sulfur hexafluoride (SF₆), and mixtures thereof.

Claim 33 (canceled)